

## **ABSTRACT**

### **COMPOSITIONS AND METHODS FOR SELECTIVELY ETCHING TITANIUM NITRIDE**

Compositions useful for the selective removal of titanium nitride and/or photoresist etch residue materials relative to metal conducting, e.g., tungsten, and insulating materials from a microelectronic device having same thereon. The removal compositions contain at least one oxidant and one etchant, may contain various corrosion inhibitors to ensure selectivity.

(No Suitable Figure)